

Search Notes



Application No.

10/720,851

Examiner

Stephen W. Smoot

Applicant(s)

UESAWA, FUMIKATSU

Art Unit

2813

SEARCHED

| Class | Subclass | Date | Examiner |
|---------|----------|-----------|----------|
| 438 | 620 | 6/25/2004 | SWS |
| 438 | 637 | 6/25/2004 | SWS |
| 438 | 640 | 6/25/2004 | SWS |
| 438 | 669 | 6/25/2004 | SWS |
| 438 | 671 | 6/25/2004 | SWS |
| 438 | 673 | 6/25/2004 | SWS |
| 438 | 780 | 6/25/2004 | SWS |
| Updated | Above | 12/6/2004 | SWS |
| 438 | 978 | 12/6/2004 | SWS |
| Updated | Above | 3/2/2005 | SWS |
| Updated | Above | 6/8/2005 | SWS |
| | | | |
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INTERFERENCE SEARCHED

| Class | Subclass | Date | Examiner |
|---------------|----------|----------|----------|
| | | | |
| | | | |
| | | | |
| Same as Above | | 6/8/2005 | SWS |

SEARCH NOTES (INCLUDING SEARCH STRATEGY)

| | DATE | EXMR |
|---|------------------------|------|
| Key Words: Mask - Organic, Tapered, Photoresist, Resist, Aperture, Hole Opening; | 6/25/2004 | SWS |
| Dual Hard Mask; Low Temperature Etching. | 6/25/2004 | SWS |
| Updated Above Search | 12/6/2004 | SWS |
| Updated Above Search | 3/2/2005 | SWS |
| Updated Above Search | 6/8/2005 | SWS |
| Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB | 6/25/2004; 12-6-04; | SWS |
| | 3-2-05; 8 6-8-05 | SWS |
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